

Electronic supplementary information

A graphene-Mo₂C heterostructure for a highly responsive broadband photodetector

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Heterostructure	Condition	Responsivity AW^{-1}	Response time	wavelength	Ref.
Graphene- Cu_{3-x}P	$V_{\text{sd}} = 1 \text{ V}$ 405 nm	$1.59 \times 10^5 \text{ AW}^{-1}$	540 ms	405-1550 nm	1
Graphene-Au NRs	$V_{\text{sd}} = 1 \text{ V}$ 1300nm	$4 \times 10^4 \text{ AW}^{-1}$	8200 ms	400-1310 nm	2
Graphene- MoTe_2	$V_{\text{sd}} = 1 \text{ V}$ 1064 nm	972 AW^{-1}	78 ms	532-1064 nm	3
Perovskite-organic	$V_{\text{sd}} = -0.1 \text{ V}$ 720 nm	0.43 AW^{-1}	56 ns	300-1000 nm	4
Graphene- Mo_2C	$V_{\text{sd}} = 1 \text{ V}$ 405 nm	9381.4 AW^{-1}	5.4 ms	405-1550	This work

Table S1. Comparison between graphene- Mo_2C device and other similar devices based on graphene or other composite materials.

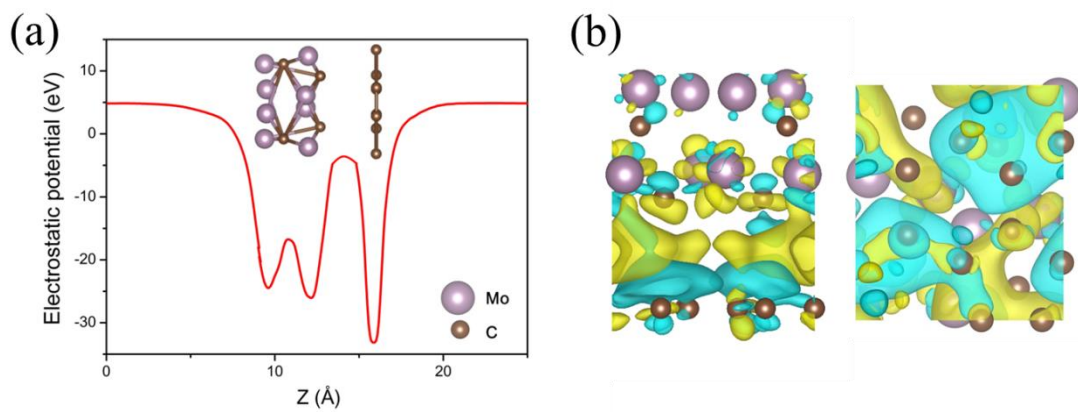


Figure S1. a) Effective electrostatic potential profile of graphene-Mo₂C heterostructure. The corresponding structure diagram is shown in the illustration. b) Side view and top view of charge density difference for graphene-Mo₂C heterostructure. The blue areas indicate the depletion of electrons and yellow areas indicate the accumulation of electrons.

Computing method:

The first-principles calculation method based on density functional theory is adopted, and the whole calculation process is performed in Vienna ab initio simulation package (VASP). The van der Waals correction of opt-PBE is taken into account in the calculation. The plane-wave basis cutoff energy is uniformly set at 400 eV. The atomic positions were optimized until the forces on atoms were less than 10^{-2} eV Å⁻¹, and the criterion of 10^{-6} eV per unit cell was sufficiently strict to obtain during the structural relaxation. To eliminate the spurious interaction between the periodically repeated images of the slabs, the vacuum layer was set to more than 20 Å. The 6×6×1 Monkhorst-Pack K mesh was for the geometric optimization and state calculation.

Notes and references

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